

ABSTRACT

APPARATUS FOR SUPPLYING GAS FOR WAFER CONTAINER

The present invention relates to an apparatus for supplying a gas for a wafer container, which injects a purge gas into a wafer container accommodating and transferring a wafer. The apparatus includes a stage part on which the wafer container is seated, a gas entrance part disposed in correspondence to a position of each of a gas inlet and a gas outlet, which are defined in the wafer container, and including a housing coupled to the stage part and a nozzle inserted into the housing to ascend and descend in the housing and in which a flow path, through which a purge gas flows, is defined, a first driving part ascending and descending while connected to the nozzle and providing an ascending driving force for lifting the nozzle, and a second driving part elastically supporting the first driving part to provide an elastic force in a direction in which the first driving part ascends. As the driving force sufficient to lift the nozzle is supplied by including the first and second driving parts, the nozzle may smoothly ascend when the wafer container is separated from an upper portion of the nozzle, to prevent the purge gas from being wasted and enhance productivity of a wafer processing process.

Figure 3